Accepted Manuscript

Fracture toughness of Mo2BC thin films: Intrinsic toughness versus system toughening

R. Soler, S. Gleich, C. Kirchlechner, C. Scheu, J.M. Schneider, G. Dehm

PII:	S0264-1275(18)30394-0
DOI:	doi:10.1016/j.matdes.2018.05.015
Reference:	JMADE 3915
To appear in:	Materials & Design
Received date:	30 January 2018
Revised date:	4 May 2018
Accepted date:	7 May 2018

Please cite this article as: R. Soler, S. Gleich, C. Kirchlechner, C. Scheu, J.M. Schneider, G. Dehm, Fracture toughness of Mo2BC thin films: Intrinsic toughness versus system toughening. The address for the corresponding author was captured as affiliation for all authors. Please check if appropriate. Jmade(2017), doi:10.1016/j.matdes.2018.05.015

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.



ACCEPTED MANUSCRIPT

Fracture toughness of Mo₂BC thin films: Intrinsic toughness versus system toughening

R. Soler^a, S. Gleich^a, C. Kirchlechner^{a,*}, C. Scheu^a, J. M. Schneider^{a,b}, G. Dehm^{a*}

^aMax-Planck-Institut für Eisenforschung GmbH, Max-Planck-Strasse 1, 40237 Düsseldorf, Germany ^bMaterials Chemistry, RWTH Aachen University, Kopernikusstraße 10, 52074 Aachen, Germany

> *corresponding authors: Dr. Christoph Kirchlechner / Prof. Dr. Gerhard Dehm Max-Planck-Institut für Eisenforschung GmbH Max-Planck-Straße 1 40237 Düsseldorf c.kirchlechner@mpie.de / dehm@mpie.de

Abstract

The fracture behaviour and microstructure evolution of sputtered Mo₂BC films as a function of their deposition temperature is studied. Bipolar pulsed direct current magnetron sputtering was used to deposit Mo₂BC thin films onto Si (100) wafers at substrate temperatures ranging from 380 to 630 °C. Microstructural characterization by transmission electron microscopy revealed that increasing the deposition temperature induces larger and more elongated grains, and a higher degree of crystallinity, transitioning from a partially amorphous to a fully crystalline film. The intrinsic fracture toughness of the Mo₂BC films was studied by focussed ion beam milled micro-cantilever bending tests. A mild dependency of the intrinsic fracture toughness on the substrate deposition temperature was found. Fractograph analysis showed that the fracture behaviour was dominated by intergranular fracture or by fracture within the amorphous regions. Additionally, nanoindentation based fracture toughness measurements were used to probe the fracture behaviour of the Mo₂BC/Si system, where residual stresses define the 'apparent' fracture toughness of the system. Depending on the substrate deposition temperature either compressive or tensile residual stresses developed in the films. This causes a relative change in the system toughness by up to one order of magnitude. The fracture experiments clearly reveal that notched cantilevers provide intrinsic toughness values of a material, while nanoindentation probes the toughness of the entire coating-substrate system. The combination of both techniques provides valuable design information for enhancing fracture resistance of Mo₂BC films.

Keywords: hard coating, fracture toughness, residual stress, nanoindentation, single beam cantilever, transmission electron microscopy.

Download English Version:

https://daneshyari.com/en/article/7216915

Download Persian Version:

https://daneshyari.com/article/7216915

Daneshyari.com